

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A pattern formation method of forming a film pattern by disposing liquid droplets of a functional solution on a substrate, the method comprising the following steps performed in the following order:

filling a passage, including a liquid droplet ejection head to dispose the liquid droplets and a conduit to feed the functional solution to the liquid droplet ejection head, with purified water;

filling the passage with a solvent dissolving both a solvent contained in the functional solution and the purified water;

filling the passage with the solvent contained in the functional solution;

filling the passage with the functional solution;

forming banks corresponding to the film pattern on the substrate; and

disposing the liquid droplets into grooves between the banks with the liquid droplet ejection head.

2. (Currently Amended) A pattern formation method of forming a film pattern by disposing liquid droplets of a functional solution on a substrate, the method comprising the following steps performed in the following order:

filling a passage, including a liquid droplet ejection head filled with a predetermined storage solution and a conduit to feed the functional solution to the liquid droplet ejection head, with a first solvent dissolving the storage solution;

filling the passage with a second solvent dissolving both the first solvent and a solvent contained in the functional solution;

filling the passage with the solvent contained in the functional solution;

filling the passage with the functional solution;

forming banks corresponding to the film pattern on the substrate; and

disposing the liquid droplets into grooves between the banks with the liquid droplet ejection head.

3. (Original) The pattern formation method according to Claim 1, the method further comprising:

filling the passage with the functional solution after filling the passage with the solvent contained in the functional solution.

4. (Original) The pattern formation method according to Claim 1, the functional solution exhibiting electrical conductivity by thermal or optical treatments.

5. (Original) A device manufacturing method, comprising:
forming a film pattern on a substrate, the film pattern formed on the substrate by the pattern formation method according to Claim 1.

6. (Withdrawn) An electro-optical device, comprising:
a device manufactured by using the device manufacturing method according to Claim 5.

7. (Withdrawn) An electronic apparatus, comprising:
the electro-optical device according to Claim 6.